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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/764,520	01/27/2004	Tokihiro Nishihara	020494A	9968
23850 7	590 12/22/2005		EXAM	INER
ARMSTRONG, KRATZ, QUINTOS, HANSON & BROOKS, LLP			ESTRADA, MICHELLE	
1725 K STREE	ET, NW			D. DED MU (DED
SUITE 1000			ART UNIT	PAPER NUMBER
WASHINGTO	N, DC 20006		2823	

DATE MAILED: 12/22/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

•		EV.				
	Application No.	Applicant(s)				
	10/764,520	NISHIHARA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Michelle Estrada	2823				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING D.  Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  If NO period for reply is specified above, the maximum statutory period of Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be timwill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nety filed the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 27 Ja	<u>anuary 2004</u> .					
2a)☐ This action is <b>FINAL</b> . 2b)☒ This						
3) Since this application is in condition for alloward	nce except for formal matters, pro	secution as to the merits is				
closed in accordance with the practice under E	Ex parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.				
Disposition of Claims						
4) Claim(s) 27-31 is/are pending in the application	4) Claim(s) <u>27-31</u> is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.	Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>27-31</u> is/are rejected.						
7) Claim(s) is/are objected to.	Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/o	Claim(s) are subject to restriction and/or election requirement.					
Application Papers						
9)☐ The specification is objected to by the Examine	er.					
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.						
Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the correct	tion is required if the drawing(s) is obj	ected to. See 37 CFR 1.121(d).				
11)☐ The oath or declaration is objected to by the Ex	caminer. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
<ul><li>12) Acknowledgment is made of a claim for foreign</li><li>a) All b) Some * c) None of:</li></ul>	priority under 35 U.S.C. § 119(a)	-(d) or (f).				
1. Certified copies of the priority document						
2. Certified copies of the priority document	• •					
3. Copies of the certified copies of the prior	•	ed in this National Stage				
application from the International Bureau	* * * * * * * * * * * * * * * * * * * *					
* See the attached detailed Office action for a list of the certified copies not received.						

U.S. Patent and Trademark Office PTOL-326 (Rev. 7-05)

1) Notice of References Cited (PTO-892)

Paper No(s)/Mail Date 1/27/04.

2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)

Attachment(s)

6) Other: \_\_\_\_\_.

4) Interview Summary (PTO-413)
Paper No(s)/Mail Date. \_\_\_\_\_.

5) Notice of Informal Patent Application (PTO-152)

### **DETAILED ACTION**

# Claim Objections

Claim 28 is objected to because of the following informalities: The term "deep" in claim 28 is a relative term which renders the claim indefinite. The term "deep" is not defined by the claim, the specification does not provide a standard for ascertaining the requisite degree, and one of ordinary skill in the art would not be reasonably apprised of the scope of the invention. If Applicant intends any particular strength or duration of the RIE it should be clearly recited. Appropriate correction is required.

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 27, 28, 30 and 31 are rejected under 35 U.S.C. 103(a) as being unpatentable over Lin et al. (6,924,583) in view of Sumi (6,402,303).

Lin et al. disclose preparing a substrate (401) including a first surface and a second surface opposite to said first surface; forming a resonator assembly which includes a first electrode (404) held in contact with said first surface, a piezoelectric layer (403) formed on the first electrode and a second electrode (402) formed on the piezoelectric layer; and forming a cavity on the substrate, the

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cavity being disposed at a location corresponding to the resonator assembly, the cavity being opened in said first surface and said second surface (See fig. 4); wherein the cavity includes a side surface extending in a substantially perpendicular direction to said first surface.

Lin et al. do not specifically disclose forming the cavity by dry etching the substrate.

Sumi discloses dry etching a cavity on a substrate (20), which has a piezoelectric formed therein (Col. 10, lines 1-5).

It would have been within the scope of one of ordinary skill in the art to combine the teachings of Lin et al. and Sumi to enable the cavity formation step of Lin et al. to be performed according to the teachings of Sumi because one of ordinary skill in the art would have been motivated to look to alternative suitable methods of performing the disclosed cavity formation step of Lin et al. and art recognized suitability for an intended purpose has been recognized to be motivation to combine. See MPEP 2144.07.

Re claim 28, Sumi disclose wherein the dry etching is deep-RIE.

Re claim 30, Sumi discloses wherein a groove for dividing the substrate is also formed by etching at the cavity-forming step.

Re claim 31, Lin et al. disclose preparing a substrate (401) including a first surface and a second surface opposite to said first surface; forming a resonator assembly which includes a first electrode (404) held in contact with said first surface, a piezoelectric layer (403) formed on the first electrode and a second electrode (402) formed on the piezoelectric layer; and forming a cavity on the

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substrate, the cavity being disposed at a location corresponding to the resonator assembly, the cavity being opened in said first surface and said second surface (See fig. 4); wherein the first electrode and the piezoelectric layer are partially exposed to the cavity at the cavity-forming step.

Lin et al. do not specifically disclose forming the cavity by dry etching the substrate.

Sumi discloses dry etching a cavity on a substrate (20), which has a piezoelectric formed therein (Col. 10, lines 1-5).

It would have been within the scope of one of ordinary skill in the art to combine the teachings of Lin et al. and Sumi to enable the cavity formation step of Lin et al. to be performed according to the teachings of Sumi because one of ordinary skill in the art would have been motivated to look to alternative suitable methods of performing the disclosed cavity formation step of Lin et al. and art recognized suitability for an intended purpose has been recognized to be motivation to combine. See MPEP 2144.07.

Claim 29 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lin et al. in view of Sumi as applied to claims 27, 28, 30 and 31 above, and further in view of Hasegawa et al. (2002/0011986).

The combination does not disclose further comprising the step of bonding a cover substrate to said second surface so as to close the cavity.

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Hasegawa et al. disclose further comprising the step of bonding a cover substrate (506) to said second surface so as to close the cavity (See fig. 9 and page 5, [0069].

It would have been within the scope of one of ordinary skill in the art to combine the teachings of Lin et al., Sumi and Hasegawa et al. to enable the cover substrate formation step of Hasegawa et al. to be performed in the process of the combination to allow the piezoelectric to vibrate and supply a voltage amplified alternating signal to the lower electrode.

#### Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Estrada whose telephone number is 571-272-1858. The examiner can normally be reached on Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 571-272-2800.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Michelle Estrada Patent Examiner Art Unit 2823

ME December 19, 2005